



North America Microlithography Committee Meeting Summary and Minutes

NA Standards SEMICON West 2013 Meetings
Tuesday, July 9th, 2013
9:30 AM – 11:30 AM (PST)
San Francisco Marriott Marquis Hotel in San Francisco, California

Next Committee Meeting

The next NA Microlithography Committee meeting will be held at the San Francisco Marriott Marquis Hotel in conjunction with SEMICON West 2014 on July 8-11, 2014 in San Francisco, California. The meeting date, time, and room are to be determined and subject to change.

The latest schedule and meeting details will be updated at the SEMI Standards Calendar of Events: http://www.semi.org/en/Standards/CalendarEvents

Table 1 Meeting Attendees

Italics indicate virtual participants

Co-Chairs: Wes Erck (Wes Erck & Associates), Rick Silver (NIST)

SEMI Staff: Michael Tran

Company	Last	First	Company	Last	First
Synopsys	Gookassian	John			
U.A. Associates	Hartsough	Larry			
Wes Erck & Associates	Erck	Wes	SEMI NA	Tran	Michael

Table 2 Leadership Changes

None.

Table 3 Ballot Results

None.

Table 4 Authorized Activities

None.

Table 5 Authorized Ballots

None.

Table 6 New Action Items

Item #	Assigned to	Details	
2013Jul#01	Thomas Germer	Thomas Germer (NIST) to ask Rick Silver to disband the TF.	
2013Jul#02	Wes Erck	Wes Erck to work with John Gookassian for a BNF sample of the XML.	
2013Jul#03		Michael Tran to ask if SEMI P24 has been downloaded with in the last 6 years and follow with John Gookasian and Wes Erck to if See if anyone is using SEMI P24 could help upd it.	
2013Jul#04	Michael Tran	Michael Tran to contact John Zimmerman and Long He about updating SEMI P5.	





Table 7 Previous Meeting Actions Items

Item #	Assigned to	Details	Status
2013Feb#01	Wes Erck	Work with David Bouldin on some of the inputs received from Justin Benore for documents 5120, 5121, 5122, 5123, 5124, and 5125.	Open
2013Feb#02	Michael Tran	Send Wes Erck and John Gookassian documents 5121, 5124, 5125, 5126, and 5127 for their review.	Open
2013Feb#03	Michael Tran	Ask Thomas Germer to ask Rick silver whether to keep the TF	Open
2013Feb#04	Pawitter Mangat	See if someone from GLOBALFOUNDRIES has any suggestions for new syntax to be implemented in the P10 XML schema files.	Open
2013Feb#05	Pawitter Mangat	Will review SEMI P34 (Square Photomask Substrates) with others to see if it should be revised or reapproved.	Open
2013Feb#06	Michael Tran	Send Wes Erck and Rick Silver the committee reviewed document list for 5 year review.	Done.
2012Jul#02	Michael Tran	Work with Wes Erck on documents needing five years reviews.	OPEN, ongoing
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2011Jul #01	Wes Erck	Work with Justin Benore (MGC Pure Chemicals America) on inputs submitted for ballots (5120, 5121, 5122, 5123, 5124, and 5125).	OPEN, see Action Item: 2013Feb#01
2011Jul #02	Wes Erck	Work with John Gookassian (Synopsys) on inputs submitted for ballots (5121, 5124, 5125, 5126, and 5127).	OPEN, see Action Item: 2013Feb#02
2011Jul #04	Rick Silver	Ask Thomas Germer (NIST) about the current status of the Standards for Scatterometry TF.	OPEN, see Action Item: 2013Feb#03

1 Welcome, Reminders, and Introductions

1.1 Wes Erck (Wes Erck & Associates), committee co-chair, called the meeting to order at 10:09 AM PST. The meeting reminders on antitrust issues, intellectual property issues and holding meetings with international attendance were reviewed. Attendees introduced themselves.

Attachment: 01, Required Meeting Elements

2 Review of Previous Meeting Minutes

2.1 The committee reviewed the minutes of the previous meeting.

Motion: To approve the previous meeting minutes from SEMICON West 2012 as written.

By / 2nd: John Gookassian (NIST) / Larry Hartsough (U.A. Associates)

Discussion: None.

Vote: 3-0 in favor. Motion passed.

Attachment: 02, Previous Meeting Minutes (SPIE 2013)





3 Liaison Reports

- 3.1 Japan Micropatterning Committee
- 3.1.1 Michael Tran (SEMI N.A.) gave the Japan Micropatterning Committee Report. The key items were as follows:
 - Iwao Higashikawa (Toshiba) stepped down as committee co-chair
 - o Morihisha Hoga (DNP) will take over as co-chair August 28, 2013
 - Meeting Information
 - The last meeting was April 09, 2013 during Japan Spring Meetings 2013 at SEMI Japan, Tokyo, Japan
 - The next meeting will be August 28, 2013 during Japan Summer Meetings 2013 at SEMI Japan, Tokyo, Japan
 - Ballot Results
 - Passed committee review
 - Doc.#5535, Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology
 - Doc.#5536, Reapproval of P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS)
 - Mask Data Format for Mask Tools TF
 - The TF is drafting document #5229, Revision to SEMI P44, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools
 - SEMI Japan Micropatterning contact, Naoko Tejima, SEMI Japan (ntejima@semi.org)

Attachment: 03, Japan Micropatterning Report (West 2013)

- 3.2 SEMI Staff Report
- 3.2.1 Michael Tran (SEMI NA) gave the SEMI NA Staff Report. The key items were as follows:
 - Some Upcoming SEMI Major Events
 - SEMICON Taiwan 2013 / LED Taiwan 2013
 - September 4-6, 2013 in Taipei
 - o SEMICON Europa 2013 / Plastic Electronics Exhibition and Conference
 - October 8-10, 2013 Dresden, Germany
 - SEMICON Japan 2013
 - December 4-6, 2013 in Chiba
 - Upcoming North America Standards Meeting
 - NA Standards Fall 2013 Meetings
 - October 28-31, 2013 in San Jose and Santa Clara, California
 - Inviting local companies willing and able to host some of the meetings to maintain oneweek format
 - Cycle 6-2013 Critical Dates for SEMI Standards Ballots





- o Cycle 6, 2013
 - Ballot Submission Date: August 15, 2013
 - Voting Period Starts: August 29, 2013
 - Voting Period Ends: September 30, 2013
- SEMI Standards Publications
 - Standards published from April 2013 to June 2013:
 - New Standards: 16
 - Revised Standards: 11
 - Reapproved Standards: 15
 - Withdrawn Standards: 0
 - There are a total of 887 SEMI Standards in portfolio and that includes 94 Inactive standards
- SEMI N.A. Standards staff contact: Michael Tran, mtran@semi.org

Attachment: 04, SEMI North America Standards Staff Report (West 2013)

4 Ballot Review

None.

5 Subcommittee & Task Force Reports

- 5.1 Terminology of Metrology TF
- 5.1.1 Wes Erck reported Jim Potzick, the TF leader would like to keep it open.
- 5.2 Standards for Scatterometry TF
- 5.2.1 Wes Erck reported Thomas Germer (NIST) to ask Rick Silver to disband the TF.

Action Item: 2013Jul#01, Thomas Germer (NIST) to ask Rick Silver to disband the TF.

- 5.3 Extreme Ultraviolet (EUV) Mask TF
- 5.3.1 No update was given.
- 5.4 Mask Orders (P10) TF
- 5.4.1 Wes Erck reported for the TF. The TF submitted a SNARF (#5561) to revise SEMI P10 since the last update. The TF still needs a volunteer from the foundry side to help with XML schema files for the P10 syntax. Wes Erck will work with John Gooskasian (Synopsis) to translate a handwritten sample of the P10 syntax to the Backus-Naur Form (BNF). The BNF will then be used to translate the P10 syntax to XML.

Action Item: 2013Jul#02, Wes Erck to work with John Gookassian for a BNF sample of the XML.

- 5.5 Data Path TF
- 5.5.1 No update was given.





- 5.6 Extreme Ultraviolet (EUV) Fiducial Mark TF
- 5.6.1 No update was given.

6 Old Business

- 6.1 Five-Year Review
- 6.1.1 Michael Tran (SEMI NA) presented to the committee a list of documents that were due for 5 year review. The committee reviewed the list and provided that status of each document:

Document	Title	Status
SEMI P1-0708E	EMI P1-0708E Specification for Hard Surface Photomask Substrates	
SEMI P2-0308	SEMI P2-0308 Specification for Chrome Thin Films for Hard Surface Photomasks	
SEMI P3-0308	SEMI P3-0308 Specification for Photoresist/E-Beam Resist for Hard Surface Photoplates	
SEMI P5-0704	Specification for Pellicles	John Z./Long He see if there should be more work done for EUV. Wes said it's fine for older technology.
SEMI P6-88 (Reapproved 0707)	Specification for Registration Marks for Photomasks	Inactive maybe.
SEMI P11-0308 Test Method for Determination of Total Normality for Alkaline Developer Solutions		Inactive. No support.
SEMI P12-0997 Determination of Iron, Zinc, Calcium, Magnesium, Coppel Boron, Aluminum, Chromium, Manganese, and Nickel in Photoresists by Inductively Coupled Plasma Emission Spectroscopy (ICP)		Ballot Failed in 2011. Inactive.
SEMI P13-91 (Reapproved 1104)	Determination of Sodium And Potassium in Positive Photoresists by Atomic Absorption Spectroscopy	Ballot Failed in 2011. Inactive at West 13.
SEMI P14-0997	Determination of Tin in Positive Photoresists by Graphite Furnace Atomic Absorption Spectroscopy	Ballot Failed in 2011. Inactive at West 13.
SEMI P15-92 (Reapproved 1104)	Determination of Sodium and Potassium in Positive Photoresist Metal Ion Free (MIF) Developers by Atomic Absorption Spectroscopy	Ballot Failed in 2011. Inactive at West 13.
SEMI P16-92 (Reapproved 1104)	Determination of Tin in Positive Photoresist Metal Ion Free (MIF) Developers by Graphite Furnace Atomic Absorption Spectroscopy	Ballot Failed in 2011. Inactive at West 13
SEMI P17-92 Determination of Iron, Zinc, Calcium, Magnesium, Copper, Boron, Aluminum, Chromium, Manganese, and Nickel in Positive Photoresist Metal Ion Free (MIF) Developers by Inductively Coupled Plasma Emission Spectroscopy (ICP)		Ballot Failed in 2011. Inactive at West 13.





Document	Title	Status
SEMI P18-92 (Reapproved 1104)	Specification for Overlay Capabilities of Wafer Steppers	Forward the document to Rick Silver. Need someone to help define the verbiages in the document and supply a suitable drawing.
SEMI P19-92 (Reapproved 0707)	Specification for Metrology Pattern Cells for Integrated Circuit Manufacture	Rich Allen and Rick looking at it.
SEMI P24-94 (Reapproved 1104)	CD Metrology Procedures	Ask David Bouldin (co- chair Metrics committee) to help revise it or adjust the scope. John Gookasian and Wes Erck will work with him.
SEMI P28-96 (Reapproved 0707)	Specification for Overlay-Metrology Test Patterns for Integrated-Circuit Manufacture	Rick looking and deciding inactive or not.
SEMI P34-0200 (Reapproved 0707)	Specification for 230 mm Square Photomask Substrates	Pawitter will send and forward to some others to see if it should be revised or reapproved.
SEMI P35-1106	Terminology for Microlithography Metrology	Japan reapproved it. Waiting to be published.
SEMI P39-0308	Specification for Open Artwork System Interchange Standard (OASIS)	Send to Tom Grebinski. Let him know it has to be balloted for reapproval.

Action Item: 2013Jul#03, Michael Tran to ask if SEMI P24 has been downloaded with in the last 6 years and

follow up with John Gookasian and Wes Erck to if See if anyone is using SEMI P24 could help

update it.

Action Item: 2013Jul#04, Michael Tran to contact John Zimmerman and Long He about updating SEMI P5.

7 New Business

7.1 *None*.

8 Action Item Review

- 8.1 Open Action Items
- 8.1.1 Michael Tran (SEMI) reviewed the open action items. These can be found in the Open Action Items table at the beginning of these minutes.
- 8.2 New Action Items
- 8.2.1 Michael Tran (SEMI) reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.





9 Next Meeting and Adjournment

9.1 The next NA Microlithography Committee meeting will be held at the San Francisco Marriott Marquis Hotel in conjunction with SEMICON West 2014 on July 8-11, 2014 in San Francisco, California. The meeting date, time, and room are to be determined and subject to change.

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9.2 Having no further business, a motion was made to adjourn the NA Microlithography committee meeting on July 9th, 2013.

Respectfully submitted by:

Michael Tran Senior Standards Engineer SEMI North America Phone: 1-408-943-7019 Email: mtran@semi.org

Minutes approved by:

ates approved by:			
Wes Erck (Wes Erck & Associates), Co-chair			
Rick Silver (NIST), Co-chair			

Table 8 Index of Available Attachments #1

#	# Title		Title
01 Required Meeting Elements		03	Japan Micropatterning Report (West 2013)
02 Previous Meeting Minutes (SPIE 2013)		04	North America Standards Staff Report (West 2013)

^{#1} Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Michael Tran at the contact information above.